



## **Prof. Takeo Watanabe**

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Takeo Watanabe is now Full Professor, Director of Center for EUVL (CEL) at Laboratory of Advanced Science and Technology for Industry (LASTI), and Special Assistant to the President, University of Hyogo. He is expert of the EUV lithographic technologies for electronic devices and works in the EUVL field more than 30 years.

He started his work for R&D of 64MBit DRAM technologies at the Central Development and Research Laboratory of Sharp Corporation in Japan, 1990. He has experience of electron beam, i-line, KrF, X-ray proximity lithograph, and dry etching processing. And from 1993, he started his research work of X-ray projection lithography (present EUV lithography) at the national project of METI in Japan. After that he joined the LASTI Himeji Institute of Technology (present University of Hyogo, Japan) in 1996. The fundamental R&D of EUV lithography related research has been carried out at LASTI since 1996. The LASTI has been operating the NewSUBARU synchrotron light facility which is the largest synchrotron facility operated by university in Japan since in January 2000. And many contributions related to the technology of EUV resist, EUV mask, and EUV optics etc. have being carried at NewSUBARU.

He has authored over 250 technical papers, many patents, and received many awards.

He is the President of the International Conference of Photopolymer Science and Technology (ICPST). He is also the Conference Chair of the International Conference on Photomask Japan.

He is also a committee member of IEEE International Roadmap of Devices and Systems.